

Electrochemically Exfoliated Platinum Dichalcogenide Atomic Layers for High-Performance Air-Stable Infrared Photodetectors

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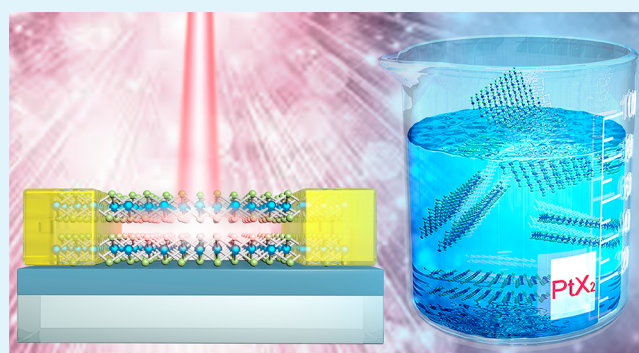
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Supporting Information

ABSTRACT: Platinum dichalcogenide (PtX_2), an emergent group-10 transition metal dichalcogenide (TMD) has shown great potential in infrared photonic and optoelectronic applications due to its layer-dependent electronic structure with potentially suitable bandgap. However, a scalable synthesis of PtSe_2 and PtTe_2 atomic layers with controlled thickness still represents a major challenge in this field because of the strong interlayer interactions. Herein, we develop a facile cathodic exfoliation approach for the synthesis of solution-processable high-quality PtSe_2 and PtTe_2 atomic layers for high-performance infrared (IR) photodetection. As-exfoliated PtSe_2 and PtTe_2 bilayer exhibit an excellent photoresponsivity of 72 and 1620 mA W^{-1} at zero gate voltage under a 1540 nm laser illumination, respectively, approximately several orders of magnitude higher than that of the majority of IR photodetectors based on graphene, TMDs, and black phosphorus. In addition, our PtSe_2 and PtTe_2 bilayer device also shows a decent specific detectivity of beyond 10^9 Jones with remarkable air-stability (>several months), outperforming the mechanically exfoliated counterparts under the laser illumination with a similar wavelength. Moreover, a high yield of PtSe_2 and PtTe_2 atomic layers dispersed in solution also allows for a facile fabrication of air-stable wafer-scale IR photodetector. This work demonstrates a new route for the synthesis of solution-processable layered materials with the narrow bandgap for the infrared optoelectronic applications.

KEYWORDS: IR photodetectors, electrochemical exfoliation, bilayer PtSe_2 , bilayer PtTe_2 , air-stable



INTRODUCTION

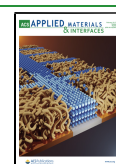
Two-dimensional (2D) layered semiconductors have demonstrated great potential in future photonic and optoelectronic applications due to their flexible atomically thin structures and outstanding layer-dependent electronic and optical properties.^{1–6} In particular, infrared (IR) photodetectors have been widely used in remote sensing, optical communications, and IR imaging.⁷ Therefore, tremendous efforts have been devoted to search for promising 2D candidates for IR photodetection with high photoresponsivity and specific detectivity including graphene,^{8–12} TMD,^{13–16} and black phosphorus (BP).^{17–20} For example, it has been reported that graphene exhibits an ultrawide band detection because of its semimetallic nature. Unfortunately, the photodetection performance of graphene is limited largely by its low absorption coefficient and short lifetime of the photogenerated carriers.^{11,21,22} Alternatively, engineering graphene-based heterostructures has been exploited to further enhance the performance of graphene-based photodetection.²³ In contrast, semiconducting TMDs with sizable bandgaps and strong absorption at specific wavelengths are considered as appealing alternatives beyond graphene for

photodetection. To date, most reports focus on the exploration of group-6 TMDs with bandgaps ranging between 1 and 2.5 eV, and thus their optoelectronic devices mainly work in the visible light regime.^{24–26} In addition to TMDs, BP with a high carrier mobility demonstrates layer-dependent direct bandgaps ranging from the visible to infrared regime, which has sparked enormous research interest in the photodetection in near and mid-IR range. However, the extreme air-sensitivity of BP poses a formidable challenge for its practical application under ambient conditions.^{19,20} Therefore, the development of new approaches for the synthesis of air-stable 2D semiconductors with suitable narrow bandgap for the infrared optoelectronic and photonic applications is highly desired.

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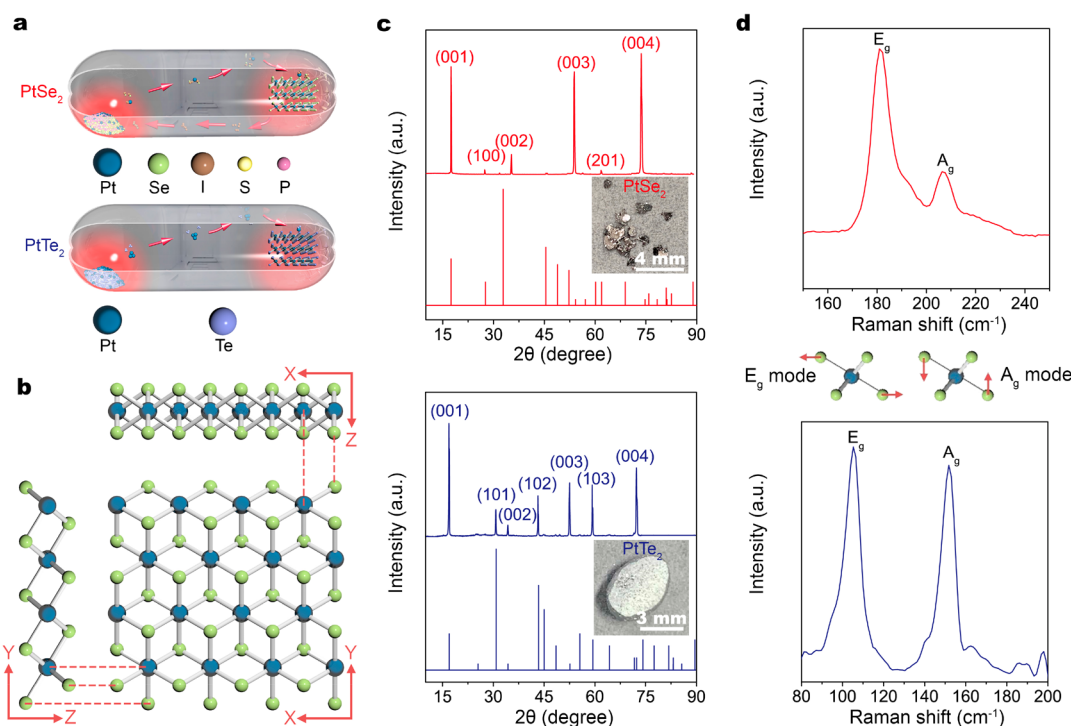


Figure 1. Synthesis of PtSe₂/PtTe₂ crystals through CVT method. (a) Schematic diagram of the experimental setup for the growth of PtSe₂/PtTe₂ crystals. (b) Top and side view of the crystal structure of 1T-PtSe₂/PtTe₂ (Blue: Pt, Green: Se/Te). (c) X-ray diffraction spectra of 1T-PtSe₂/PtTe₂ crystals (up) compared with the 1T-PtSe₂/PtTe₂ standard card of PDF#18-0970/PDF#18-0977 (bottom). Inset: the photograph of the synthesized PtSe₂/PtTe₂ crystals. (d) Raman spectra of PtSe₂ and PtTe₂ crystals.

Platinum dichalcogenide (PtX₂), a group-10 noble TMD, has been recently recognized as a remarkable candidate for the infrared photonic and optoelectronic applications owing to its environmental stability and unique layer-dependent electronic and optical properties.^{27–33} Monolayer and bilayer PtSe₂ are predicted to have an indirect bandgap of ~ 1.2 and ~ 0.2 eV, respectively, while trilayer PtSe₂ and beyond have a zero-bandgap.^{28,34} Similarly, monolayer PtTe₂ is predicted to possess an indirect bandgap of ~ 0.4 eV, while bilayer PtTe₂ and beyond have a zero bandgap.³⁴ Recently, mechanically exfoliated bilayer PtSe₂ has been demonstrated as a photoactive material with a strong light absorption from visible to mid-IR range.²⁷ Interestingly, negative photoconduction is observed in ultrathin PtSe₂ film due to a photogating effect at Si/SiO₂ interface.³⁵ To further propel their practical application, a facile and scalable synthesis of 2D PtX₂ atomic flakes with controlled thickness is highly demanded. The current synthetic strategy mainly relies on chemical vapor deposition (CVD), or sonication-assisted liquid phase exfoliation (LPE) by probe sonication.^{36–39} The mechanical exfoliation and chemical vapor deposition methods often yield multilayer structures, owing to their relatively larger interlayer binding energies as compared to other common TMD materials.^{36,40–42} Sonication-assisted liquid phase exfoliation can produce few-layer PtX₂ flakes with small domain sizes that typically limit the performance of as-fabricated devices.³⁹ By contrast, a facile electrochemical exfoliation approach offers a rapid production of solution-processable few-layer 2D materials with micron lateral size at a large quantity and low cost.^{17,43–46}

To this end, we report a facile electrochemical exfoliation approach for a rapid production of solution-processable high quality atomically thin PtSe₂ and PtTe₂ flakes. Bulky organic

tetraalkylammonium (TAA) cations are used as the intercalant for the mild cathodic exfoliation of bulk PtSe₂ and PtTe₂ crystals to avoid the sample oxidation which would occur during the anodic exfoliation of 2D materials.^{17,47,48} Under the optimized condition, bilayer PtSe₂ flakes can be readily exfoliated from bulk crystals with a yield of $\sim 44\%$. Furthermore, the photoresponse analysis based on as-exfoliated PtSe₂ and PtTe₂ bilayer flakes reveals outstanding performance with a high photoresponsivity of 72 mA W^{-1} and 1.62 A W^{-1} and decent specific detectivity of 1.44×10^9 and 2.11×10^9 Jones at zero gate voltage under the laser illumination of 1540 nm with a power density of 15.9 mW cm^{-2} and 0.16 W cm^{-2} , respectively.

RESULTS AND DISCUSSION

The Growth and Characterization of Bulk PtSe₂ and PtTe₂ Crystals. Figure 1a illustrates the growth process of the crystals in a quartz tube based on the chemical vapor transport (CVT) method (see details in the Experimental Section).^{27,28,49} Representative PtX₂ single crystals with a lateral dimension of several mm are shown in the inset of Figure 1c. 1T-PtX₂ crystal possesses a typical hexagonal atomic structure under $P\bar{3}m1$ space group (Figure 1b).^{27,30,50} X-ray diffraction (XRD) measurement of as-grown samples further confirms the crystal structure of PtSe₂ and PtTe₂ crystals (Figure 1c), consistent with the previous reports.^{27,51} In addition, the presence of sharp peaks (001) indicates a good crystal quality of bulk PtSe₂ and PtTe₂ crystals. Raman spectrum acquired from the as-grown PtSe₂ (PtTe₂) crystals (Figure 1d) reveal two dominating features around 180 and 206.4 cm^{-1} (105.2 and 151.8 cm^{-1}), attributed to the E_g and the A_g modes corresponding to in-plane and out-of-plane phonon modes, respectively.^{28,30,52,53} Therefore, both XRD data and Raman

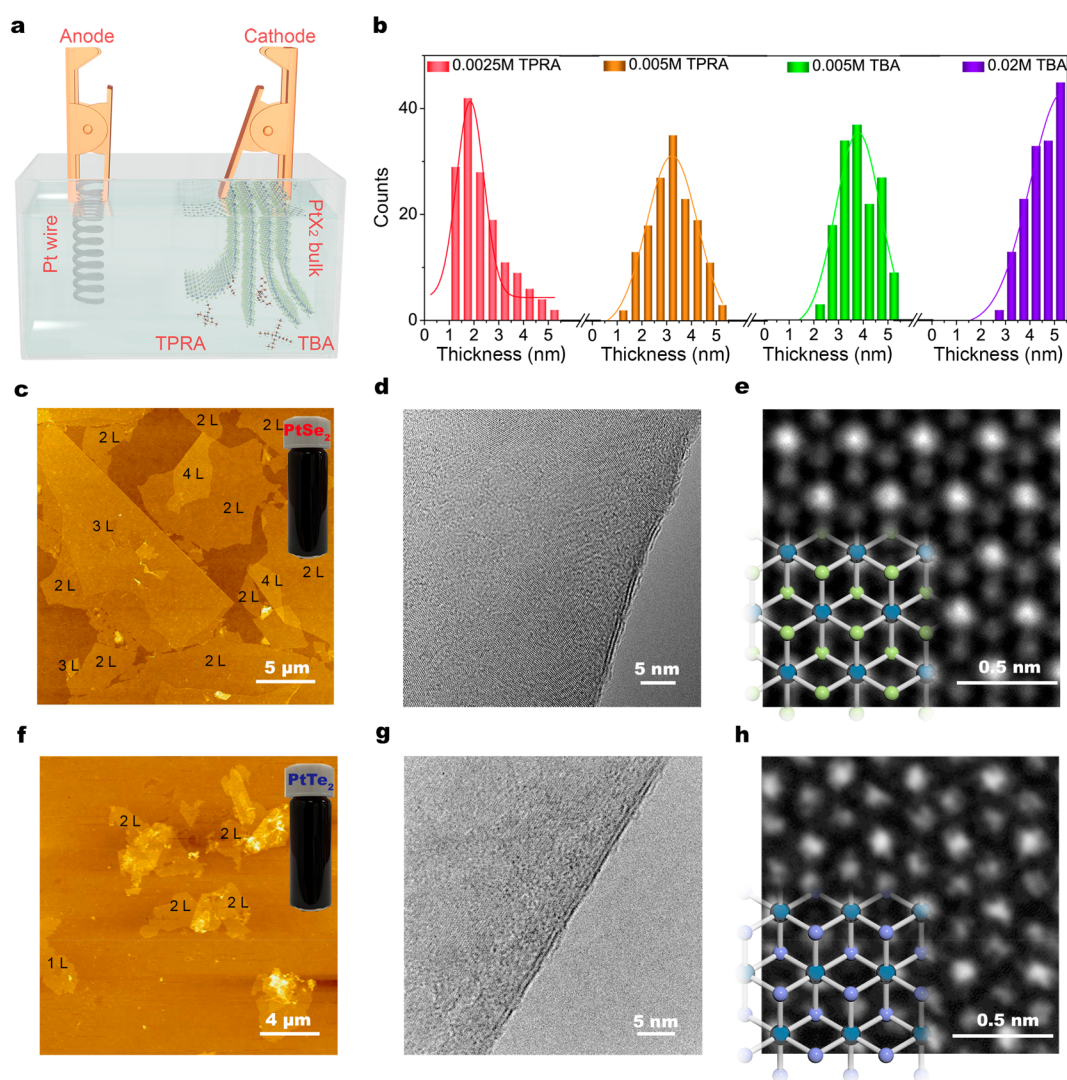


Figure 2. Characterization of the electrochemically exfoliated PtSe₂/PtTe₂ flakes. (a) Experimental setup for electrochemical exfoliation. (b) Statistics of the thickness of the PtSe₂ flakes exfoliated in DMSO solution under different conditions. (c,d) AFM image of the PtSe₂ (c) and PtTe₂ (f) flakes on SiO₂/Si substrate. The inset: photograph of the solution dispersion of exfoliated flakes. (d,e,g,h) TEM (d,g) and atomic resolution STEM-ADF (e,h) images of exfoliated PtSe₂ (d,e) and PtTe₂ (g,h).

spectrum demonstrate a good crystal quality of bulk PtSe₂ and PtTe₂.

The Electrochemical Exfoliation of PtSe₂ and PtTe₂ Bulk Crystals into Atomically Thin Flakes. Figure 2a illustrates the electrochemical exfoliation setup consisting of bulk PtSe₂ and PtTe₂ (cathode), Pt wire (anode), and organic TAA cations dissolved in dimethyl sulfoxide (DMSO) solvent (electrolyte).^{17,54} It is noted that the thickness distribution of exfoliated PtSe₂ flakes can be controlled by tuning the length of alkyl chain of the TAA salts and their concentration as well as the solvent and cathodic voltage applied (Figure 2b). An optimal yield of bilayer PtSe₂ (~44%) can be achieved in electrolyte consisting of a 0.0025 M tetrapropylammonium (TPRA) in DMSO at the cathodic voltage of 6 V (refer to details in the Supporting Information (SI) Section 1 and Figure S2).¹⁷ The thickness of the majority of as-exfoliated PtSe₂/PtTe₂ flakes is determined to be 1.2–1.5 nm by AFM imaging (Figure 2c,f and SI Figure S3), corresponding to the expected thickness of a bilayer PtSe₂/PtTe₂.²⁷ Raman spectra of different PtSe₂ and PtTe₂ flakes (SI Figure S4) reveal that E_g mode shows a blue shift when the flake becomes

thinner.^{39,50,52,53,55,56} The feature at ~230 cm⁻¹ for bilayer-PtSe₂ flake is attributed to longitudinal optical (LO) modes.⁵² The images of aberration-corrected scanning transmission electron microscopy–annular dark field (STEM-ADF) reveal a nearly perfect atomic crystal structure with each Pt atom (bright spot) surrounded by six dimmer Se/Te atoms, in agreement with the octahedral structure with the lattice constant of ~3.8 Å and ~4.0 Å expected for 1T-phase PtSe₂ and PtTe₂, respectively (Figure 2d,e,g,h).^{27,51}

The Device Performance of a Bilayer PtSe₂/PtTe₂-Based Photodetector. As shown in Figure 3a–c, first-principles calculations predict the layer-dependent electronic structures of PtSe₂. Bilayer PtSe₂ possesses an indirect bandgap of ~0.23 eV, suitable for the infrared optoelectronics, in contrast to monolayer (an indirect bandgap of ~1.18 eV) and trilayer or above (semimetal).^{34,57} We then fabricated a bilayer PtSe₂-based device to probe its photodetection performance in the IR regime (Figure 3g). The device adopts a typical field effect transistor configuration (Figure 3h) consisting of a heavily doped Si substrate as the back-gate and the Cr/Au (5 nm/60 nm) electrodes deposited by the electron-beam

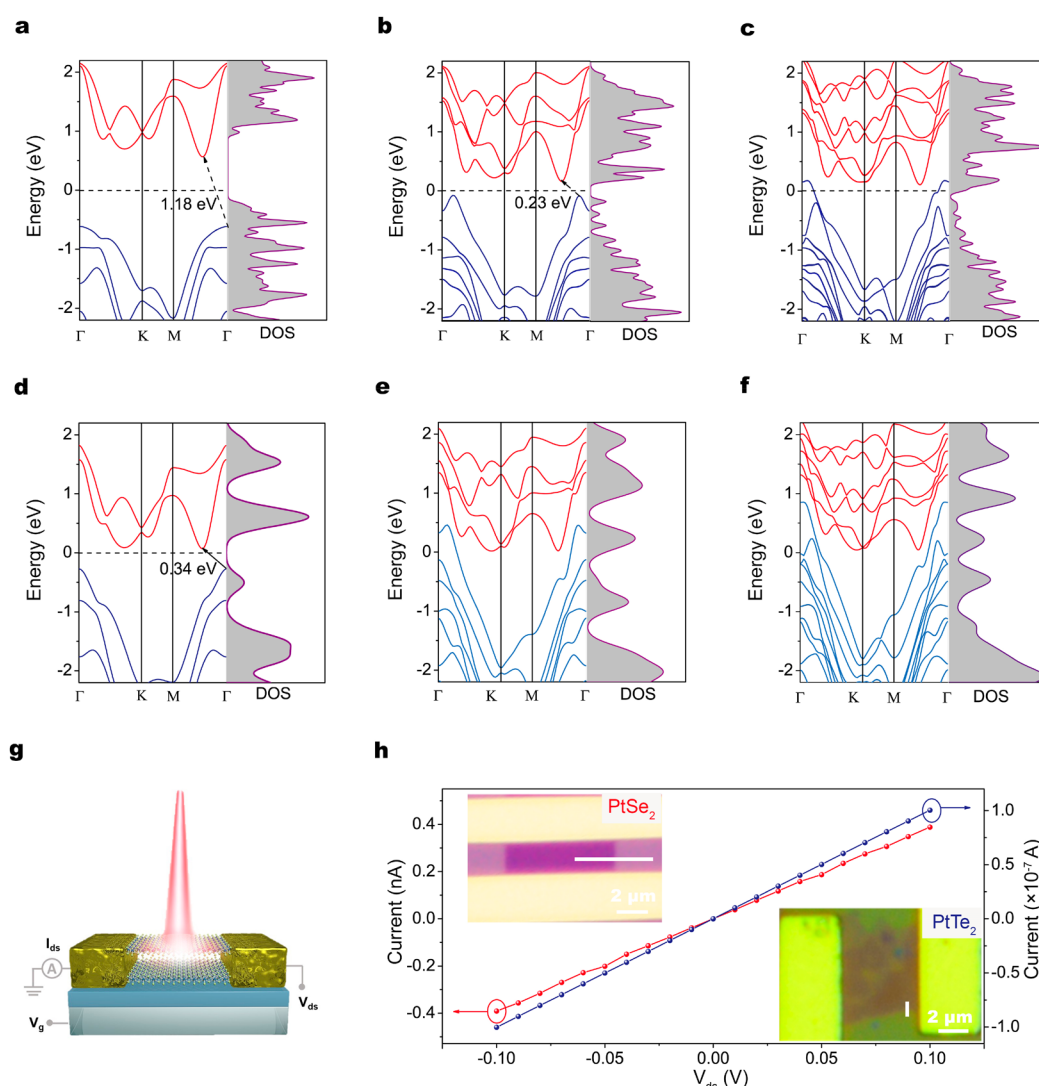


Figure 3. Theoretical calculations of band structure and density-of-states (DOS) of layered PtSe₂ and PtTe₂ and I_{ds} – V_{ds} characteristics of bilayer-PtSe₂/PtTe₂ phototransistor devices. (a,b) Calculated band structure and DOS of (a) monolayer, (b) bilayer, and (c) trilayer PtSe₂ by first-principles calculations. (d–f) Calculated band structure and DOS of (d) monolayer, (e) bilayer, and (f) trilayer PtTe₂ by first-principles calculations. (g) Schematic diagram of the cross-section structure of the bilayer-PtSe₂/PtTe₂ device. (h) I_{ds} – V_{ds} characteristics of the bilayer-PtSe₂/PtTe₂ FET under zero gate voltage and V_{ds} in the range of -0.1 – 0.1 V. Inset: Optical microscope images of the bilayer-PtSe₂/PtTe₂ devices.

evaporation. As depicted in Figure 3h, a linear I_{ds} – V_{ds} curve measured in a small voltage range ($-0.1 < V_{ds} < 0.1$ V) implies an ohmic contact between bilayer PtSe₂ and metal electrodes. Furthermore, the contact resistance between the metal electrodes and the flake is determined to be $(5.8 \pm 0.5) \times 10^{-3} \Omega \text{ cm}^2$ (SI Figure S5) according to the transmission line method (TLM).⁵⁸ The ohmic contact between the metal electrodes and the bilayer flake is beneficial for a high photodetection performance of bilayer PtSe₂-based device.⁵⁹

Subsequently, the photodetection performance of a bilayer PtSe₂-based FET is investigated in the infrared region. First, the power density of a 1064 nm laser is modulated to record the photocurrent at $V_{ds} = 0.5$ V for the time-resolved photoresponse measurements as shown in Figure 4a (noted that I_{ds} – V_{ds} characteristics are shown in SI Figure S6a). It is observed that the generated photocurrent (defined as $I_{ph} = I_{illum} - I_{dark}$) increases from ~ 125 to ~ 555 pA when the laser power density increases from 0.39 to 2.66 W cm⁻² (Figure 4d and SI Figure S6a), which obeys a power law relationship ($I_{ph} \propto P^\alpha$, where P is the incident power density).^{14,27,60} The

deviation from a linear relationship is possibly ascribed to the photogating dominated gain mechanism involving the generation, interaction, trapping and recombination of photo-carriers.^{10,24,61} Here, the power exponent α of the PtSe₂-based photodetector is extracted to be 0.781, consistent with the fact that low-dimensional materials-based photodetectors usually exhibit a power exponent α ranging from 0 to 1.^{8,9,60}

The photoresponsivity and detectivity are considered as two important parameters for photodetectors.^{14,27,60,62,63} The photoresponsivity and the detectivity can be defined using the following equations:^{14,62,63}

$$R = \frac{I_{ph}}{P_{in}} \quad (1)$$

$$D^* = \frac{\sqrt{AR}}{\sqrt{2eI_d}} \quad (2)$$

where I_{ph} , P_{in} , A , e , I_d denote the photocurrent, the incident laser power, the effective device area, the electronic charge and

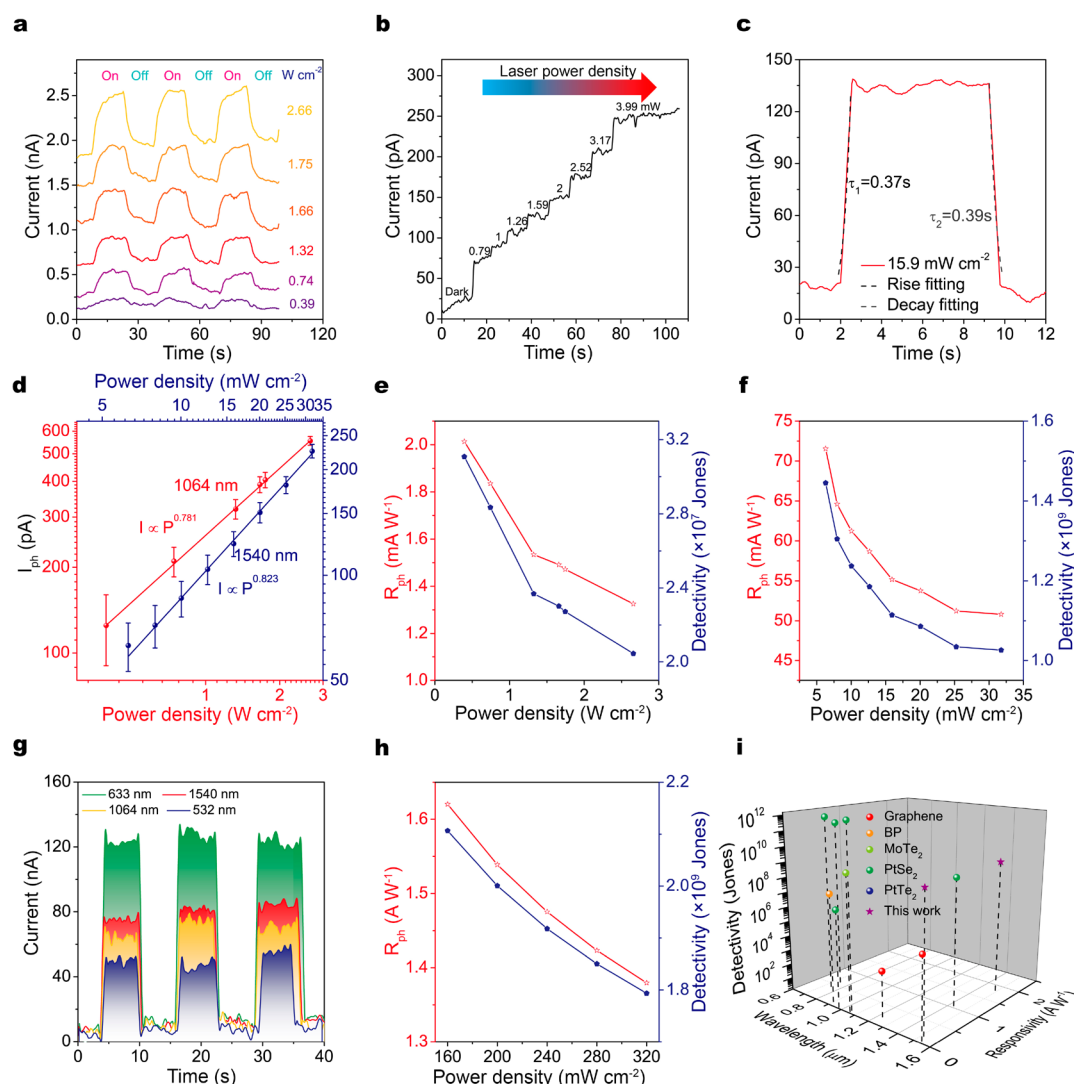


Figure 4. Optoelectronic properties of the bilayer-PtSe₂ and bilayer-PtTe₂ devices in the infrared region. (a,b) Time-resolved photocurrent of bilayer-PtSe₂ device for a bias voltage of 0.5 V and zero gate voltage excited by 1064 and 1540 nm laser illumination with different laser power density, respectively. (c) The rise and decay time of the photocurrent of bilayer-PtSe₂ device under the laser illumination with the wavelength of 1540 nm determined by fitting. (d) Power dependence of the photocurrent of the bilayer-PtSe₂ device recorded at $V_{ds} = 0.5$ V under 1064 and 1540 nm laser illumination. (e,f) Power dependence of the photoresponsivity and detectivity of the PtSe₂ device under 1064 and 1540 nm laser illumination, respectively. (g) Time-resolved photocurrent of bilayer-PtTe₂ device for a bias voltage of 0.5 V and zero gate voltage excited by 532 nm, 633 nm, 1064 nm, and 1540 nm laser illumination with a power density of 0.16 W cm⁻². (h) Power dependence of the photoresponsivity and detectivity of the PtTe₂ device under 1540 nm laser illumination. (i) Comparison with the reported infrared photodetector based on 2D materials.

the dark current, respectively. The laser power density dependent measurement reveals that both R and D^* decrease as the power density of incident laser increases (Figure 4e). The maximum of the photoresponsivity reaches 2 mA W⁻¹ with a power density of 0.39 W cm⁻², much lower than other reported TMD-based photodetectors.^{10,15,19} This is presumably due to a low light absorption coefficient at 1064 nm for the electrochemically exfoliated bilayer PtSe₂. The absorption measurement indeed reveals that the exfoliated PtSe₂ flakes exhibit a local absorption maximum between 1400 and 1600 nm (SI Figure S7 and S8), which suggests an increase of bandgap of the majority of bilayer flakes in the solution, presumably due to the presence of residual intercalated species in the interlayer space, consistent with the AFM height profile measured over bilayer flakes (SI Figure S9a). We then investigated the photodetection performance of the same device under the same laser power density (15.9 mW cm⁻²) at

the wavelength of 1540 nm, which reveals a dramatically enhanced photocurrent up to ~123 pA. Furthermore, the rise and decay time could be determined by fitting curves with the following equations:⁶⁴

$$I_{\text{rise}} = I_0 + A_1 \exp\left(\frac{t - t_1}{\tau_1}\right) \quad (3)$$

$$I_{\text{decay}} = I_0 + A_2 \exp\left(-\frac{t - t_2}{\tau_2}\right) \quad (4)$$

where τ is the rise/decay time constant and t_1 or t_2 is the time of laser switching-on or switching-off, respectively. Here, τ_1 and τ_2 are determined to be ~0.37 s for rise time and ~0.39 s for decay time respectively (Figure 4c), superior to that at the wavelength of 1064 nm. In addition, the time period of the current range from 10% to 90% in rising and decaying is

determined to be ~ 0.38 s, consistent with the above fitted results (SI Figures S10 and S17 in Section 2). Figure 4d shows an apparent rise of the photocurrent against the laser power density. A standard fitting (based on $(I_{ph} \propto P^\alpha)$) gives rise to a power exponent α of 0.823. This is probably due to the fact that high energy defect states cannot trap the photogenerated carriers at 1540 nm, leading to an enhanced photocurrent.^{24,60} As depicted in Figure 4f, an increase of the incident laser power density reduces the photoresponsivity and detectivity, consistent with the previous report on other 2D materials based photodetectors.^{29,60} The presence of trap states results in a higher carrier recombination rate under a larger laser power density, leading to a shorter average carrier lifetime and thus a lower photogain and photoresponsivity.^{14,60} Moreover, the PtSe₂ device exhibits a high photoresponsivity of 72 mA W⁻¹ under the laser power density of 6.29 mW cm⁻² at 1540 nm, nearly 2 orders of magnitude higher than that at 1064 nm. Furthermore, as-fabricated PtSe₂ bilayer device shows a negligible decrease in the photocurrent after its storage in air for 3 months, suggesting a good stability (SI Figure S11). In addition, the structural anisotropy in PtSe₂ monolayer endows its properties with a polarization sensitive photodetection.^{13,65} Indeed, the photocurrent varies with the change of polarization angle and reaches the maximum and minimum value at 0° and 90°, respectively (SI Figure S12). The linear dichroism properties of PtSe₂ will expand its potential application for future photonic and optoelectronic devices.

Apart from PtSe₂, monolayer PtTe₂ also possesses an indirect bandgap of ~ 0.34 eV, in contrast to bilayer and trilayer PtTe₂ (zero bandgap). This suggests that PtTe₂ atomic layers may serve as another promising candidate for IR photodetection (Figure 3d–f and SI Figure S13).⁶⁶ Figure 3h shows a linear I_{ds} – V_{ds} curve measured in a small voltage range ($-0.1 < V_{ds} < 0.1$ V), implying an ohmic contact between bilayer PtTe₂ and metal electrodes in the bilayer-PtTe₂ device. Figure 4g shows that the bilayer-PtTe₂ photodetector demonstrates excellent photodetection performance in visible and infrared regime (SI Table S1). In detail, the bilayer-PtTe₂ device exhibits an excellent photoresponsivity of 1.62 A W⁻¹ and the detectivity of 2.11×10^9 Jones under the laser power density of 0.16 W cm⁻² at 1540 nm with excellent stability (Figure 4h and SI Figures S14 and S15). The photoresponsivity of bilayer-PtTe₂ device at 1540 nm is about 1 order of magnitude higher than that of bilayer-PtSe₂ device, while the detectivity of both devices lies in the same order of magnitude. The photoresponsivity and specific detectivity of the PtSe₂ and PtTe₂ devices in the IR regime is also superior or comparable to that of similar photodetectors made by graphene,^{11,12} BP,²⁰ and TMD materials,^{16,28,29,32,66,67} as shown in Figure 4i and SI Table S2. The photodetection performance of PtX₂-based photodetectors (e.g., rise/decay time and photoresponsivity) is comparable to that of the conventional IR photodetectors of PbS quantum dots (QDs).^{68,69}

To further bridge the gap between the lab demonstration and practical applications, we utilize the high-solution processability of the exfoliated flakes to fabricate the large-scale and air-stable photodetectors on the quartz substrates. As shown in SI Figure S16a, the PtSe₂ and PtTe₂ thin film is deposited onto the substrate via drop-cast techniques. The time-resolved photoresponse measurement of the large-scale device (SI Figure S16) reveals that the photocurrent also increases, while the rise and decay time of the photoresponse

decrease with an increase of the incident laser power. Furthermore, the large-scale photodetector shows a remarkable air-stability (>several months tested). However, the rise and decay time are much longer than that of the photodetector based on a single flake, which is presumably due to the weak penetrability of the infrared photons that influence the laser absorption of the underlying flakes.

CONCLUSIONS

In summary, a facile and general electrochemical approach is developed to exfoliate the PtSe₂ and PtTe₂ bulk crystals into high-quality atomically thin PtSe₂ and PtTe₂ flakes with a high bilayer yield under the optimized conditions. Furthermore, as-exfoliated bilayer PtSe₂ flake delivers an excellent photodetection performance with a high photoresponsivity of 0.072 A W⁻¹ and the detectivity of 1.44×10^9 Jones at 1540 nm with a laser power density of 15.9 mW cm⁻², which can maintain its device performance more than 3 months. As-exfoliated PtTe₂ bilayer exhibits an excellent photoresponsivity of 1.62 A W⁻¹ and the detectivity of 2.11×10^9 Jones at 1540 nm with a laser power density of 0.16 W cm⁻², about 4 orders of magnitude higher than the photoresponsivity of graphene-based device. In addition, the high solution-processability of exfoliated flakes allows for the fabrication of the large-scale PtSe₂ and PtTe₂ thin film devices with a high stability and a good photodetection performance. Therefore, this work offers a promising route for the scalable synthesis of air-stable PtX₂ atomic layers with controlled thickness for the superior photodetection performance in the IR regime under ambient conditions.

EXPERIMENTAL SECTION

Synthesis of PtSe₂ and PtTe₂ Crystals. The experimental set up shown in Figure 1a was used to grown bulk PtSe₂ through CVT method.^{27,28,49} A mixture of Pt, Se, P, and S powders (the total weight of 350 mg) with a molar ratio of 1:2:1:3 plus iodine (17 mg, act as the transport gas) were sealed in a vacuum (10^{-6} Torr) quartz tube, which was placed into a muffle furnace subsequently. The temperature of the muffle furnace was first kept at 900 °C for 40 h and then at 700 °C for 5 days. PtSe₂ bulk crystals are obtained after cooling to the room temperature. Bulk PtTe₂ crystal was also grown through CVT method. A mixture of Pt and Te powders with a molar ratio of 1:2.03 (the total weight is 301 mg) were sealed in quartz tube under the vacuum and put into the furnace. The temperature of the furnace was gradually increased to 1000 °C at the speed of 1 °C min⁻¹ and kept at 1000 °C for 2 days, followed by a slow increase to 1150 °C (Kept for 60 min) at the speed of 1 °C min⁻¹. Finally, the furnace was cooled down to the room temperature at the speed of 1 °C min⁻¹.

Device Fabrication. Bulk PtSe₂/PtTe₂ crystals with typical dimensions of $2 \times 2 \times 1$ mm³ (length \times width \times thickness) were fixed on a Pt clip for a cathodic exfoliation at -6 V (vs Pt counter electrode) for 20 min (SI Figure S1). The bilayer yield was determined via AFM statistics. The bilayer yield was determined via the statistical analysis of the AFM height of as-exfoliated flakes. Specifically, exfoliated PtSe₂/PtTe₂ flakes in electrolyte were subjected to centrifugation at 3000 rpm (503.6 g) to separate them from unexfoliated bulks. The upper dispersion was dropped onto the SiO₂/Si substrates. We then measured the thickness of more than 150 individual flakes on the SiO₂/Si substrates by AFM imaging (SI Figure S2). The yield of bilayer flakes refers to the percentage of bilayer among all the flakes measured.¹⁷ PtSe₂/PtTe₂ bilayer device: as-exfoliated PtSe₂/PtTe₂ flakes were first deposited onto the SiO₂/Si substrate via drop-casting and then were placed in DMSO to remove residual TAA salts and subsequently were dried in a vacuum tube. The target flakes were identified by the optical microscopy (Olympus BX51 microscope) and AFM (Park XE-100 system) imaging for device fabrications. After conducting the standard photolithography

procedures, we deposited Cr/Au (5 nm/60 nm) metal electrodes by the electron-beam evaporation method. Large-scale device fabrication: the exfoliated PtSe₂/PtTe₂ solution was subjected to centrifugation for 5 min at 3000 rpm (503.6 g) to remove thick unexfoliated flakes. The following two steps were repeated three times to remove the residual TAA salts in the exfoliated solution: (1) The solution was first centrifuged for 15 min at 12 000 rpm (8.057k g); (2) Remove the supernatant in the centrifuge tube and then shake the tube several times after adding the pure DMSO solvent. After the removal of the solvent via centrifugation, the concentrated PtSe₂/PtTe₂ inks can be obtained for large-scale device fabrication. Finally, Au (60 nm) electrodes were deposited by e-beam evaporation after placing a mask onto the PtSe₂/PtTe₂ flakes deposited on the quartz substrates.

Characterization. Optical images of the exfoliated PtSe₂/PtTe₂ flakes on the substrate were obtained via an Olympus BX51 microscope. XRD measurements of the grown bulk crystals were conducted by a Bruker X-ray diffractometer system. AFM (Park XE-100 system) was used to characterize the surface morphology and thickness of the PtSe₂/PtTe₂ flakes. An aberration-corrected ARM200F, equipped with a cold field-emission gun and an ASCOR corrector operating at 80 kV was utilized to obtain atomic-resolution STEM-ADF images. In addition, Raman spectra of the bulk crystals and exfoliated PtSe₂/PtTe₂ flakes were measured with a 532 nm laser excitation with the power of ~1 mW, 100× objective lens and a dispersive grating with 2400 l/mm at room temperature (WITec Alpha 300R Raman system). The absorption data of the exfoliated PtSe₂ flakes were collected using a UV–visible spectrophotometer. The photoresponse measurements of the PtSe₂/PtTe₂-based photo-detector devices were conducted in the atmosphere with the illumination of different laser sources (a spot radius of 2 mm). The bias voltage across the channel and the drain-source current data were applied and collected respectively in a Keithley 4200 source meter system.

■ ASSOCIATED CONTENT

■ Supporting Information

The Supporting Information is available free of charge at <https://pubs.acs.org/doi/10.1021/acsami.0c20535>.

Additional information includes methods; electrochemical exfoliation current as the function of the applied electrochemical voltage; statistics histograms of the thickness of as-exfoliated PtSe₂ flakes; AFM image and line profiles of the PtSe₂ flakes on SiO₂/Si substrate; Raman spectra of few-layer and bulk PtSe₂ and PtTe₂, I_{ds} – V_{ds} characteristics of the PtSe₂-based device, absorption spectrum of the PtSe₂ flakes from UV–visible spectrophotometer, photocurrent, and absorption results under laser illumination with different wavelength ranging from 1500 to 1600 nm; line profiles of PtSe₂ and PtTe₂ flakes; stability of bilayer-PtSe₂ device in atmospheric condition; linear polarization angle dependent photocurrent, UV–vis spectrum of as-exfoliated PtTe₂ flakes dispersed in DMSO; I_{ds} – V_{ds} curves of the bilayer-PtTe₂ device; stability of bilayer-PtTe₂ device in atmospheric condition, photodetection performance of large-scale PtSe₂ and PtTe₂ devices, optoelectronic performance of PtTe₂-based device; optoelectronic performance of PtTe₂-based photodetector under the laser of various wavelength; a list of 2D materials based infrared photodetectors (PDF)

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Author Contributions

J.Lu supervised the project. Y.M., Q.Z., and J.L. performed the sample growth and device fabrications. Y.M., J.L., B.D., and Z.H. performed photodetection performance measurements. Y.M. and H.F. performed AFM measurements. H.X. and X.Z. performed TEM characterization. X.S. and K.W. contributed to the first-principles calculations. Y.M. and J.L. wrote the paper. All authors took part in the discussion and preparation of the manuscript.

Notes

The authors declare no competing financial interest.

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